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APPLICATION NO.	CONTRACT/PRIOR.	CLASS	SUBCLASS	ART UNIT	EXAMINER
09/839139	F	372	20	3815	Matthew C. Landau

APPLICANTS

Yasuyuki Nagai
Naoto Sano

TITLE

Laser oscillation apparatus, exposure apparatus, semiconductor device manufacturing method, semiconductor manufacturing factory, and exposure apparatus maintenance method

PTO-2040
12/99

ISSUING CLASSIFICATION												
ORIGINAL				CROSS REFERENCE(S)								
CLASS		SUBCLASS		CLASS	SUBCLASS (ONE SUBCLASS PER BLOCK)							
INTERNATIONAL CLASSIFICATION												

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	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims
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	(Assistant Examiner)	(Date)		
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